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United States Patent [19]

Fujimoto

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[54]	METHOD OF REMOVING COATED FILM FROM SUBSTRATE EDGE SURFACE AND APPARATUS FOR REMOVING COATED FILM		
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[57] ABSTRACT

A method of removing a coated film from an edge surface of a substrate comprising the steps of (a) forming an insulating film for protecting a circuit pattern of a substrate by pouring an insulating resin solution on a circuit-pattern formation surface of the substrate, (b) rotating the substrate having the insulating film coated thereon, (c) removing the insulating film by pouring a solvent on the edge surface of the substrate, while the substrate is being rotated, and (d) accelerating dehydration of the insulating film by taking at least one action of spraying a gas to the edge surface of the substrate and performing a local evacuation of a region in the proximity of the edge surface of the substrate while the substrate is being rotated.

18 Claims, 4 Drawing Sheets

